

Amendment and Response Under 37 C.F.R. §1.116 - Expedited Examining Procedure

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Serial No.: 09/651,702

Confirmation No.: 2471

Filed: August 30, 2000

For: **SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL AND METHODS OF
USING SAME****Amendments to the Claims**

This listing of claims replaces all prior versions, and listings, of claims in the above-identified application:

1-19. **(Canceled)**

20. **(Currently Amended)** A The composition of claim 19 comprising sulfur trioxide (SO_3) in a supercritical state, wherein the composition further comprises at least one oxidizer selected from the group consisting of sulfur dioxide (SO_2), nitrous oxide (N_2O), NO, NO_2 , ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br_2 , and oxygen (O_2), and wherein the composition is an organic material removal composition.

21. **(Previously Presented)** The composition of claim 20, wherein the at least one oxidizer is in a supercritical state.

22-24. **(Canceled)**

25. **(Previously Presented)** A composition comprising sulfur trioxide (SO_3) in a supercritical state and an oxidizer, wherein the composition is an organic material removal composition.

26. **(Canceled)**

27. **(Previously Presented)** A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO_2), ammonia (NH_3), H_2O , nitrous oxide (N_2O), carbon monoxide (CO), nitrogen (N_2), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

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a second component selected from the group consisting of sulfur dioxide (SO_2), nitrous oxide (N_2O), NO , NO_2 , ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br_2 , and oxygen (O_2); and sulfur trioxide (SO_3) in a supercritical state, wherein the composition is an organic material removal composition.

28. **(Previously Presented)** The composition of claim 27, wherein the first component is carbon dioxide.

29. **(Previously Presented)** The composition of claim 27, wherein a ratio of the first component to the total of the second component plus sulfur trioxide is about 1:100 by volume to about 100:1 by volume.

30. **(Canceled)**

31. **(Previously Presented)** The composition of claim 28, wherein a ratio of carbon dioxide:sulfur trioxide is about 10:1 by volume to about 1:1 by volume.

32. **(Previously Presented)** The composition of claim 27, wherein the first component is in a supercritical state.

33-42. **(Canceled)**

43. **(Previously Presented)** The composition of claim 27, wherein the second component is in a supercritical state.

44. **(Previously Presented)** The composition of claim 27, wherein the first component and the second component are both in supercritical states.

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**For: SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL AND METHODS OF
USING SAME****45. (Canceled)**

46. (Currently Amended) The composition of claim 20 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

47. (Previously Presented) The composition of claim 25 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

48. (Previously Presented) The composition of claim 27 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

49. (Canceled)

50. (Previously Presented) A composition comprising sulfur trioxide (SO_3) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from an object.

51. (Previously Presented) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO_2), ammonia (NH_3), H_2O , nitrous oxide (N_2O), carbon monoxide (CO), nitrogen (N_2), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

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a second component selected from the group consisting of sulfur dioxide (SO_2), nitrous oxide (N_2O), NO, NO_2 , ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br_2 , and oxygen (O_2); and sulfur trioxide (SO_3) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

52. (Canceled)**53. (Previously Presented)** A composition comprising sulfur trioxide (SO_3) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from a substrate assembly.**54. (Previously Presented)** A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO_2), ammonia (NH_3), H_2O , nitrous oxide (N_2O), carbon monoxide (CO), nitrogen (N_2), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

a second component selected from the group consisting of sulfur dioxide (SO_2), nitrous oxide (N_2O), NO, NO_2 , ozone (O_3), hydrogen peroxide (H_2O_2), F_2 , Cl_2 , Br_2 , and oxygen (O_2); and sulfur trioxide (SO_3) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

55. (New) The composition of claim 20 further comprising a substrate assembly in contact with the organic material removal composition.**56. (New)** The composition of claim 25 further comprising a substrate assembly in contact with the organic material removal composition.

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57. (New) The composition of claim 27 further comprising a substrate assembly in contact with the organic material removal composition.

58. (New) The composition of claim 50 further comprising a substrate assembly in contact with the composition for removing exposed organic material from an object.

59. (New) The composition of claim 51 further comprising a substrate assembly in contact with the composition for removing exposed organic material from an object.